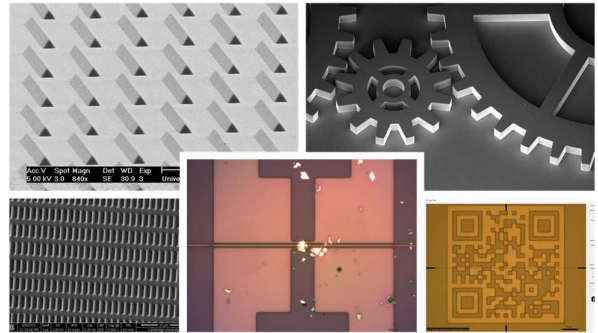


## MicroWriter ML<sup>®</sup> 3 Baby Plus



### EXCELLENT ENVIRONMENTAL FOOTPRINT

Power consumption of the machine even when exposing is comparable to that of a laptop.

### WORLDWIDE USER BASE

Over 170 laboratories around the world, including national labs and international leading Universities.

### INTUITIVE WINDOWS<sup>®</sup> USER INTERFACE

Designed for use by PhD students and post-docs in a research environment while offering high levels of flexibility.

### COMPETITIVE PRICE AND LOW COST OF OWNERSHIP

Affordable price ideal for universities and industrial R&D.

For more information, please visit us on the Web at:

[www.durhammagnetooptics.com](http://www.durhammagnetooptics.com)

The MicroWriter ML<sup>®</sup> products are a range of photolithography machines designed for rapid prototyping and small volume manufacturing in R&D laboratories and clean rooms.

Conventional approaches to photolithography are usually based on exposing through a chromium-glass mask manufactured by specialist vendors. In R&D environments it is often necessary to change the mask design frequently. Direct-write lithography tools (also known as digital mask aligners or maskless aligners) overcome this problem by holding the mask in *software*. Rather than projecting light through a physical mask, direct-write lithography uses computer-controlled optics to project the exposure pattern directly onto the photoresist.

MicroWriter ML<sup>®</sup>3 Baby Plus is a compact, high-performance, direct-write optical lithography machine which is designed to offer unprecedented value for money in a small laboratory footprint. It also has an excellent environmental footprint: power consumption of the machine even when exposing is comparable to that of a laptop.

Measuring only 70cm x 70cm at its base, the MicroWriter ML<sup>®</sup>3 Baby Plus sits on a standard laboratory bench or desk and plugs into a supplied laptop computer. Its only service requirement is a standard power socket. A light-excluding enclosure with safety interlock allows it to be used equally well in an open laboratory environment or in a clean room. Easy to use Windows<sup>®</sup> based software means most exposures can be set up and launched with just a few mouse clicks. Two different minimum feature sizes (1 $\mu$ m and 5 $\mu$ m) can be selected automatically via software. This allows non-critical parts of the exposure to be performed rapidly at 5 $\mu$ m minimum feature size while retaining high resolution writing for critical parts. The MicroWriter ML<sup>®</sup>3 Baby Plus also features an optical surface profilometer tool and an automated wafer inspection tool for examining fabricated structures.

Durham Magneto Optics

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## Key features and specifications

### FAST WRITING SPEEDS

180mm<sup>2</sup>/minute at 5µm resolution, allowing a typical a typical 50mm x 50mm area combining critical and non-critical areas to be exposed in under 30 minutes.

### PROPER AUTOMATIC LENS CHANGER

Automatically changes microscope objective lenses and exposure resolution beams using a motorised motor.

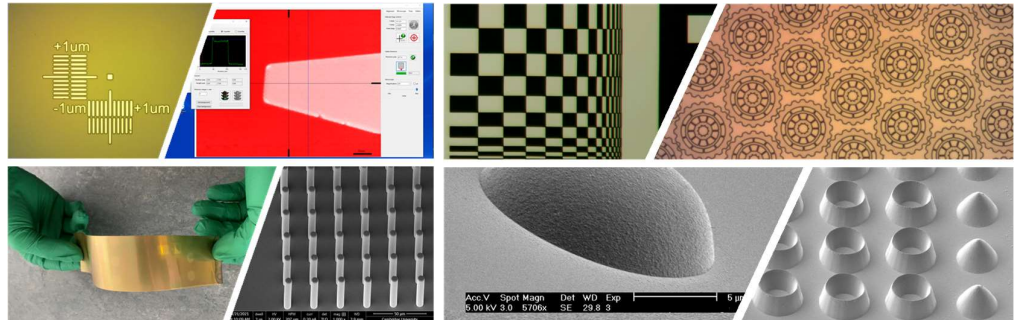
### DUAL WAVELENGTH EXPOSURE LIGHTSOURCE OPTION

Adds both 365nm light source and 405nm light source; software selectable.

### HIGH PERFORMANCE LASER INTERFEROMETER

Uses a high performance XY laser interferometer for position control.

For more information, please visit us on the Web at:  
[www.durhammagnetooptics.com](http://www.durhammagnetooptics.com)



- 149mm x 149mm maximum writing area.  
195mm x 195mm maximum writing area available as an option.
- 155mm x 155mm x 7mm maximum wafer size.  
230mm x 230mm x 15mm maximum wafer size available as an option.
- 1µm and 5µm minimum feature sizes across full writing area.  
0.6µm minimum feature size available as an option.
- Automatic selection of minimum feature size via software – no manual changing of lens required.
- 405nm long-life semiconductor light source, suitable for broadband, g- and h-line positive and negative photoresists (e.g. S1800, ECI-3000, MiR 701). Replacement 385 nm and 365nm lightsources available as option, suitable for g-, h-, and i-line photoresists (e.g. SU8). Dual wavelength option (405nm lightsource and 365nm lightsource, software selectable) available for best performance across g-, h-, and i-line photoresists.
- XY interferometer with 15nm resolution for precise motion control.
- Extremely fast writing speed - up to: 50mm<sup>2</sup>/minute (1µm minimum feature size), and 180mm<sup>2</sup>/minute (5µm minimum feature size). These allow a typical 50mm x 50mm area combining critical and non-critical areas to be exposed in under 30 minutes.
- Optical autofocus system using yellow light with real-time surface tracking module – no minimum wafer size.
- High quality infinite conjugate optical microscope with x3 aspheric objective lens, x10 Olympus plan achromatic objective lens, and yellow light illumination for alignment to lithographic markers on the wafer ( $\pm 1.0\mu\text{m}$  3 $\sigma$  alignment accuracy).
- Automatic changing between microscope magnifications via software – no manual changing of lens required. Additional x4 digital zoom can be selected in software.
- Grey scale exposure mode for 3-dimensional patterning (up to 255 grey levels).
- Export image tool (also known as “Draw Mode”) allowing exposures to be designed directly on top of an image taken from the real-time microscope.
- Software API for external interfacing and control, allowing scripting and development of more advanced automatic procedures.
- 60nm minimum addressable grid. 15nm sample stage resolution.
- Acceptable file formats: CIF, GDS2, BMP, TIFF, JPEG, PNG, GIF; Oasis, DXF, Gerber RS-274X acceptable via KLayout conversion.

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# Key features and specifications

## AUTOCALIBRATION

Autocalibration tool allowing users to check and correct calibration.

## AUTOMATIC MARKER RECOGNITION

Automatically identify the precise position of lithographic markers visible the real-time microscope.

## AUTOMATIC BARCODE GENERATION AND RECOGNITION

Automatically create the exposure pattern for 2D barcode. Developed barcode can be identified automatically.

## COMPACT LABORATORY FOOTPRINT

70cm (w) x 70cm (d) x 75cm (h).

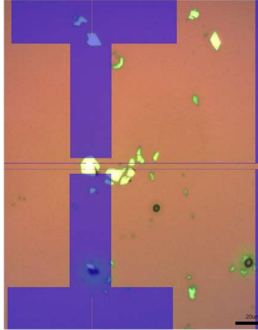
## TECHNICAL SUPPORT

International network of trained local service engineers to keep you running.

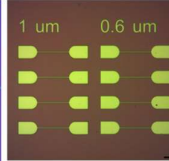
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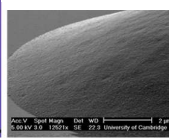
Virtual mask aligner option.



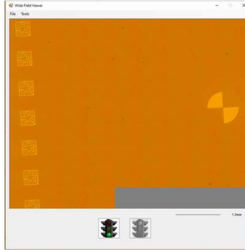
Combining resolutions.



Greyscale lithography.



Wide field viewer.



Barcode generation.



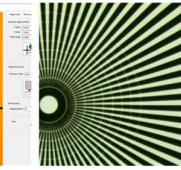
Multiple samples option.



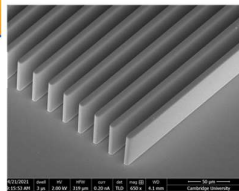
Wafer inspection.



Producing photomasks.



Structures with a high aspect ratio.



- Built-in 2-dimensional optical surface profiler (200nm thickness resolution) for examining exposed resists and MEMS process steps.
- Automatic wafer centring tool.
- Automatic wafer inspection tool allowing each die on a wafer to be imaged.
- Autocalibration tool allowing users to check and correct calibration.
- 2D barcodes can be automatically generated through software for exposures. The software can then identify the developed barcode patterns and reads the contents.
- Bulls-eye tool can automatically identify the precise position of lithographic markers visible under the real-time microscope.
- Enhance contrast tool can digitally enhance contrast and brightness of a microscope image for seeing low contrast structures.
- Estimate theta tool can automatically determine the rotation angle of the current microscope image.
- Built-in databases to store common lithographic marker positions and exposure parameters for different photoresists.
- Light-excluding enclosure with safety interlock.
- Easy to use, Windows® based control software supplied.
- Supplied with KLayout open-source mask design software ([www.klayout.de](http://www.klayout.de)).
- Supplied with pre-configured 64-bit Windows® 10/11 PC with monitor, keyboard, and mouse for 'plug and play' installation.
- Includes on-site installation by trained service technician.
- Extremely competitively priced for University and industrial R&D budgets.
- Can be later upgraded to MicroWriter ML® 3 Mesa or Pro for higher performance.
- 90-260 VAC, 50-60Hz, 4A single phase power requirement.
- External dimensions: 70cm (w) x 70cm (d) x 75cm (h), excluding computer.
- CE-marked and compliant with EN-61010.

Well-established user base around the world.



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## Examples of fabricated structures

### FRICTION CHUCK

Carefully designed friction chuck allows MEMS devices with nitride windows or other delicate substrates to be used; no minimum wafer size.

### CURVED SUBSTRATES

Perform exposures across a variety of substrates, including flat and curved forms, Si, glass, ceramic, diamond, and liquid polymers.

### PHOTOMASKS

Produce photomasks conveniently and cheaply.

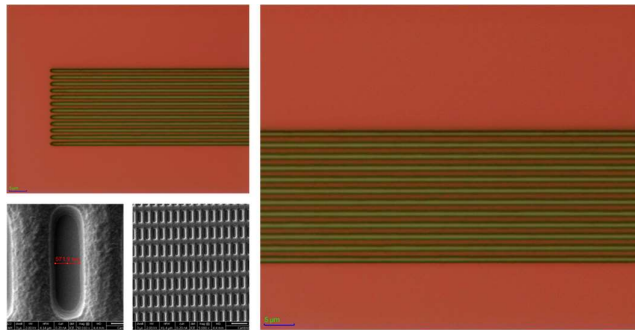
### FREE SOFTWARE UPGRADE

Receives free software upgrades for the lifetime of the machine.

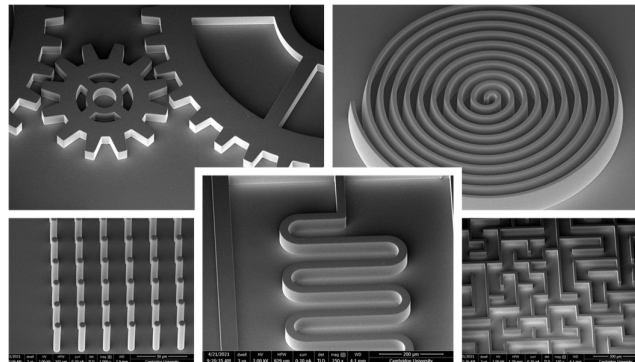
### COMPANY CULTURE AND PHILOSOPHY

We are from a research and design (R&D) background based in Cambridge, UK and the Research Triangle Park, Durham, NC, USA.

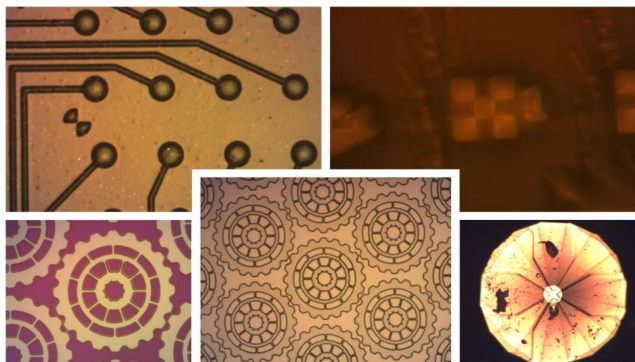
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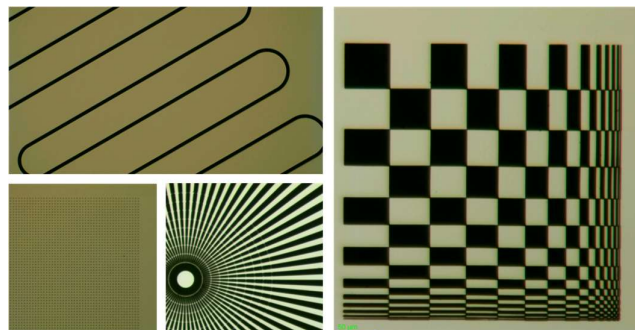
- Images of resolution-limited structures. Top left and right: Lines array with width of  $1.0\mu\text{m}$  and period of  $2.0\mu\text{m}$  on Si/Bottom antireflection coating/S1805 ( $0.5\mu\text{m}$ ). Bottom left: Lines array with width of  $0.6\mu\text{m}$  on Si/LOR/S1805 ( $0.5\mu\text{m}$ ).



- Scanning Electron Microscope images of micro-moulds. Structures were produced on a  $50\mu\text{m}$  thick SU8 layer. Aspect ratio of the dots array (bottom left) is 8.



- Optical Microscope images of patterns produced across varied types of substrates: Top left: AlN ceramic. Top right: Liquid polymer. Bottom left: Si/SiO<sub>2</sub>. Bottom middle: Glass. Bottom right: Diamond.



- Optical Microscope images of patterns produced on a photomask.

